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Oxford Instruments receives order from IMB Barcelona for Cluster System



An OIPT cluster system

Oxford Instruments Plasma Technology (OIPT), leader in producing systems and processes for etch, deposition and growth, has recently received an order from IMB Barcelona for its System100 cluster platform with two ICP-RIE process modules. The systems will be used for Aluminium etching, one of Oxford Instruments areas of expertise.

The National Centre for Microelectronics (CNM) is the largest public microelectronics research and development centre in Spain, and comprises three Institutes, including the Instituto de Microelectrónica de Barcelona, IMB-CNM.

Dra. Ana Sánchez Amores from IMB Barcelona commented, “At IMB-CNM, our facilities include an Integrated Micro and Nanofabrication clean room and other complementary laboratories for microsystems processes, device packaging and electrical characterisation. The cleanroom facility of IMB-CNM includes equipment for micro and nanofabrication processes based on silicon technology, and we will be using the OIPT Systems here for our R&D. We chose OIPT Systems as a result of a public tender process where different items have been evaluated, namely technical and economical aspects, etch process expertise with proven Systems and level of customer support offered”.

OIPT’s Sales and Customer Support Director, Mark Vosloo said, “Oxford Instruments’ tools offer excellent uniformity and high-throughput processes on a range of applications. Our flexible cluster systems are suitable both for R&D such as the IMB cleanroom installation, and for Production applications, and are backed by our extensive process library. As leaders in the industry we are delighted our systems were chosen by this prestigious Institute.”

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Issued for and on behalf of Oxford Instruments Plasma Technology Limited

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About Oxford Instruments plc

Oxford Instruments designs, supplies and supports high-technology tools, processes and solutions with a focus on research and industrial applications. It provides solutions needed to advance fundamental nanoscience research and its transfer into commercial nanotechnology applications. Innovation has been the driving force behind Oxford Instruments' growth and success for 50 years, and its strategy is to effect the successful commercialisation of these ideas by bringing them to market in a timely and customer-focused fashion.

The first technology business to be spun out from Oxford University fifty years ago, Oxford Instruments is now a global company with over 1,200 staff worldwide and a listing on the London Stock Exchange (OXIG). Its objective is to be the leading provider of new generation tools and systems for research and industrial sectors.

This involves the combination of core technologies in areas such as low temperature and high magnetic field environments, Nuclear Magnetic Resonance, X-ray electron and optical based metrology, and advanced growth, deposition and etching. Our products, expertise, and ideas address global issues such as energy and environmental conservation and are part of the next generation of telecommunications, energy products, environmental measures, security devices, drug discovery and medical advances.

About Oxford Instruments Plasma Technology

Oxford Instruments Plasma Technology offers flexible, configurable process tools and leading-edge processes for the precise, controllable and repeatable engineering of micro- and nano-structures. Our systems provide process solutions for nanometre layer epitaxial growth of compound semiconductor material, etching of nanometre sized features and the controlled growth of nanostructures. These solutions are based on core technologies in plasma-enhanced deposition and etch, ion-beam deposition and etch, atomic layer deposition and hydride vapour phase epitaxy. Products range from compact stand-alone systems for R&D, through batch tools and up to clustered cassette-to-cassette platforms for high-throughput production processing.